



August 27, 2001

Commissioner of Patents and Trademarks
Washington, D.C. 20231

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Subject:

Serial No. 09/919,036 09/21/00

Chun-Hong Peng, Rex Chen,
Simon Chang

AN INTELLIGENT WET ETCHING TOOL AS
A FUNCTION OF CHEMICAL CONCENTRATION,
TEMPERATURE AND FILM LOSS

Grp. Art Unit: 2812

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FEB 6 2002
TC 1700

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56. Copies of each document is included herewith.

U.S. Patent 6,004,881 to Bozada et al., "Digital Wet
Etching of Semiconductor Materials, discloses a wet chemical
digital etching technique for gallium arsenide or other
semiconductor materials.

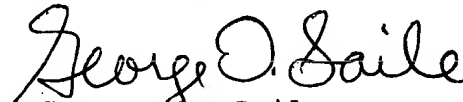
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OFFICE OF PETITIONS
DEPUTY A/C PATENTS

U.S. Patent 5,582,746 to Barbee et al, "Real Time Measurement of Etch Rate During a Chemical Etching Process", teaches a contactless method and apparatus for real-time in-situ monitoring of a chemical etching process during etching of at least one wafer in a wet chemical etchant bath.

Sincerely,


George O. Saile,
Reg. No. 19572

Doctos (Number) (Opinion)

PR-89-036

Accession Number

09/919,036

Lyricism!

Applicant: Chun-Hong Peng et al.

Filing Date

09/21/00

Group 11 Unit

2812

U. S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion or Pages, Etc.)

[illegible]

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.